

List of Publications by Citations

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

136 papers	1,261 citations	17 h-index	25 g-index
148 ext. papers	1,496 ext. citations	3.3 avg, IF	4.68 L-index

#	Paper	IF	Citations
136	Deposition of Hydrophobic Functional Groups on Wood Surfaces Using Atmospheric-Pressure Dielectric Barrier Discharge in Helium-Hexamethyldisiloxane Gas Mixtures. <i>Plasma Processes and Polymers</i> , <b>2012</b> , 9, 1168-1175	3.4	55
135	Modification of Sugar Maple ( <i>Acer saccharum</i> ) and Black Spruce ( <i>Picea mariana</i> ) Wood Surfaces in a Dielectric Barrier Discharge (DBD) at Atmospheric Pressure. <i>Journal of Adhesion Science and Technology</i> , <b>2010</b> , 24, 1401-1413	2	47
134	Improved water repellency of black spruce wood surfaces after treatment in carbon tetrafluoride plasmas. <i>Wood Science and Technology</i> , <b>2013</b> , 47, 411-422	2.5	40
133	Deposition of nanocomposite coatings on wood using cold discharges at atmospheric pressure. <i>Surface and Coatings Technology</i> , <b>2017</b> , 309, 729-737	4.4	31
132	Role of substrate outgassing on the formation dynamics of either hydrophilic or hydrophobic wood surfaces in atmospheric-pressure, organosilicon plasmas. <i>Surface and Coatings Technology</i> , <b>2013</b> , 234, 42-47	4.4	29
131	Recombination of chlorine atoms on plasma-conditioned stainless steel surfaces in the presence of adsorbed Cl <sub>2</sub> . <i>Journal Physics D: Applied Physics</i> , <b>2009</b> , 42, 055206	3	27
130	Critical review: Plasma-surface reactions and the spinning wall method. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2011</b> , 29, 010801	2.9	25
129	Determination of active species in the modification of hardwood samples in the flowing afterglow of N <sub>2</sub> dielectric barrier discharges open to ambient air. <i>Cellulose</i> , <b>2015</b> , 22, 811-827	5.5	24
128	Effects of Zn content on structural and transparent conducting properties of indium-zinc oxide films grown by rf magnetron sputtering. <i>Journal of Vacuum Science &amp; Technology B</i> , <b>2006</b> , 24, 2737		24
127	Nebulization of Nanocolloidal Suspensions for the Growth of Nanocomposite Coatings in Dielectric Barrier Discharges. <i>Plasma Processes and Polymers</i> , <b>2016</b> , 13, 981-989	3.4	24
126	Development of Organosilicon-Based Superhydrophobic Coatings through Atmospheric Pressure Plasma Polymerization of HMDSO in Nitrogen Plasma. <i>Materials</i> , <b>2019</b> , 12,	3.5	23
125	Energy dependence of ion-assisted chemical etch rates in reactive plasmas. <i>Applied Physics Letters</i> , <b>2005</b> , 87, 071502	3.4	23
124	In-Situ Surface Recombination Measurements of Oxygen Atoms on Anodized Aluminum in an Oxygen Plasma. <i>Journal of Physical Chemistry C</i> , <b>2008</b> , 112, 8963-8968	3.8	21
123	Recombination probability of oxygen atoms on dynamic stainless steel surfaces in inductively coupled O <sub>2</sub> plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2008</b> , 26, 455-461	2.9	19
122	Influence of the voltage waveform during nanocomposite layer deposition by aerosol-assisted atmospheric pressure Townsend discharge. <i>Journal of Applied Physics</i> , <b>2016</b> , 120, 053302	2.5	18
121	Effect of cryogenic temperature deposition on Au contacts to bulk, single-crystal n-type ZnO. <i>Applied Surface Science</i> , <b>2007</b> , 253, 3766-3772	6.7	17
120	Schottky barrier height of boride-based rectifying contacts to p-GaN. <i>Applied Physics Letters</i> , <b>2006</b> , 89, 132110	3.4	17

119	Influence of redeposition on the plasma etching dynamics. <i>Journal of Applied Physics</i> , <b>2007</b> , 101, 083303	2.5	17
118	Effect of Cu contamination on recombination of O atoms on a plasma-oxidized silicon surface. <i>Journal of Applied Physics</i> , <b>2009</b> , 105, 113309	2.5	16
117	Ni/Au Ohmic contacts to p-type Mg-doped CuCrO <sub>2</sub> epitaxial layers. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 142104	3.4	16
116	Kinetics driving high-density chlorine plasmas. <i>Journal of Applied Physics</i> , <b>2005</b> , 98, 063301	2.5	16
115	Sputter-etching characteristics of bariumStrontiumTitanate and bismuthStrontiumTantalate using a surface-wave high-density plasma reactor. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2002</b> , 20, 530-535	2.9	16
114	Preferential self-healing at grain boundaries in plasma-treated graphene. <i>Nature Materials</i> , <b>2021</b> , 20, 49-54	2.7	16
113	Interaction of atomized colloid with an ac electric field in a dielectric barrier discharge reactor used for deposition of nanocomposite coatings. <i>Journal Physics D: Applied Physics</i> , <b>2017</b> , 50, 075201	3	15
112	Modification of hardwood samples in the flowing afterglow of N <sub>2</sub> O <sub>2</sub> dielectric barrier discharges open to ambient air. <i>Cellulose</i> , <b>2015</b> , 22, 3397-3408	5.5	15
111	Optical emission spectroscopy of microwave-plasmas at atmospheric pressure applied to the growth of organosilicon and organotitanium nanopowders. <i>Journal of Applied Physics</i> , <b>2014</b> , 115, 113301	2.5	15
110	Improved long-term thermal stability of InGaN/GaN multiple quantum well light-emitting diodes using TiB <sub>2</sub> - and Ir-based p-Ohmic contacts. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 242103	3.4	15
109	Ohmic contacts to p-type GaN based on TaN, TiN, and ZrN. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 212107	3.4	15
108	Microfabricated SrTiO <sub>3</sub> ridge waveguides. <i>Applied Physics Letters</i> , <b>2005</b> , 86, 221106	3.4	15
107	Effect of Wood Surface Modification by Atmospheric-Pressure Plasma on Waterborne Coating Adhesion. <i>BioResources</i> , <b>2014</b> , 9,	1.3	14
106	Experimental and modeling study of O and Cl atoms surface recombination reactions in O <sub>2</sub> and Cl <sub>2</sub> plasmas. <i>Pure and Applied Chemistry</i> , <b>2010</b> , 82, 1301-1315	2.1	14
105	Dry etching of zinc-oxide and indium-zinc-oxide in IBr and BI <sub>3</sub> plasma chemistries. <i>Applied Surface Science</i> , <b>2007</b> , 253, 3773-3778	6.7	14
104	Spectroscopic diagnostics of low-pressure inductively coupled Kr plasma using a collisionalRadiative model with fully relativistic cross sections. <i>Plasma Sources Science and Technology</i> , <b>2016</b> , 25, 035025	3.5	13
103	Influence of N <sub>2</sub> , O <sub>2</sub> , and H <sub>2</sub> admixtures on the electron power balance and neutral gas heating in microwave Ar plasmas at atmospheric pressure. <i>Journal Physics D: Applied Physics</i> , <b>2019</b> , 52, 475201	3	13
102	Characterization of a microwave argon plasma column at atmospheric pressure by optical emission and absorption spectroscopy coupled with collisional-radiative modelling. <i>Physics of Plasmas</i> , <b>2019</b> , 26, 063516	2.1	13

101	Electrical characterization of the flowing afterglow of N <sub>2</sub> and N <sub>2</sub> /O <sub>2</sub> microwave plasmas at reduced pressure. <i>Journal of Applied Physics</i> , <b>2014</b> , 115, 163303	2.5	13
100	Populations of metastable and resonant argon atoms in radio frequency magnetron plasmas used for deposition of indium-zinc-oxide films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2012</b> , 30, 021301	2.9	13
99	BariumStrontiumTitanate etching characteristics in chlorinated discharges. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2003</b> , 21, 1247-1252	2.9	13
98	Low-damage nitrogen incorporation in graphene films by nitrogen plasma treatment: Effect of airborne contaminants. <i>Carbon</i> , <b>2019</b> , 144, 532-539	10.4	13
97	Electron density and temperature in an atmospheric-pressure helium diffuse dielectric barrier discharge from kHz to MHz. <i>Plasma Sources Science and Technology</i> , <b>2018</b> , 27, 035005	3.5	12
96	Time-resolved study of the electron temperature and number density of argon metastable atoms in argon-based dielectric barrier discharges. <i>Plasma Sources Science and Technology</i> , <b>2018</b> , 27, 015015	3.5	12
95	Determination of the electron temperature in plane-to-plane He dielectric barrier discharges at atmospheric pressure. <i>Plasma Sources Science and Technology</i> , <b>2016</b> , 25, 015011	3.5	12
94	High-density plasma etching of indiumZinc oxide films in Ar/Cl <sub>2</sub> and Ar/CH <sub>4</sub> /H <sub>2</sub> chemistries. <i>Applied Surface Science</i> , <b>2006</b> , 253, 2752-2757	6.7	12
93	Characterization of neutral, positive, and negative species in a chlorine high-density surface-wave plasma. <i>Journal of Applied Physics</i> , <b>2003</b> , 93, 1907-1913	2.5	12
92	Influence of substrate outgassing on the plasma properties during wood treatment in He dielectric barrier discharges at atmospheric pressure. <i>Plasma Processes and Polymers</i> , <b>2017</b> , 14, 1600172	3.4	11
91	Surface free radicals detection using molecular scavenging method on black spruce wood treated with cold, atmospheric-pressure plasmas. <i>Applied Surface Science</i> , <b>2015</b> , 359, 137-142	6.7	11
90	Deposition of fluorocarbon groups on wood surfaces using the jet of an atmospheric-pressure dielectric barrier discharge. <i>Wood Science and Technology</i> , <b>2017</b> , 51, 1339-1352	2.5	11
89	Cyclic evolution of the electron temperature and density in dusty low-pressure radio frequency plasmas with pulsed injection of hexamethyldisiloxane. <i>Applied Physics Letters</i> , <b>2015</b> , 107, 183104	3.4	11
88	Electron energy distribution functions in low-pressure oxygen plasma columns sustained by propagating surface waves. <i>Applied Physics Letters</i> , <b>2009</b> , 94, 021503	3.4	11
87	Characterization of argon dielectric barrier discharges applied to ethyl lactate plasma polymerization. <i>Journal Physics D: Applied Physics</i> , <b>2017</b> , 50, 475205	3	10
86	A combination of plasma diagnostics and Raman spectroscopy to examine plasma-graphene interactions in low-pressure argon radiofrequency plasmas. <i>Journal of Applied Physics</i> , <b>2019</b> , 126, 233302	2.5	10
85	On the Icephobic Behavior of Organosilicon-Based Surface Structures Developed Through Atmospheric Pressure Plasma Deposition in Nitrogen Plasma. <i>Coatings</i> , <b>2019</b> , 9, 679	2.9	10
84	On the validity of neutral gas temperature by N <sub>2</sub> rovibrational spectroscopy in low-pressure inductively coupled plasmas. <i>Plasma Sources Science and Technology</i> , <b>2011</b> , 20, 035016	3.5	9

83	Influence of ion mixing on the energy dependence of the ion-assisted chemical etch rate in reactive plasmas. <i>Journal of Applied Physics</i> , <b>2006</b> , 100, 063309	2.5	9
82	Dependence of the sputter-etching characteristics of strontium titanate thin films on their structural properties. <i>Applied Physics Letters</i> , <b>2004</b> , 84, 2500-2502	3.4	9
81	Deposition of anti-fog coatings on glass substrates using the jet of an open-to-air microwave argon plasma at atmospheric pressure. <i>Plasma Processes and Polymers</i> , <b>2020</b> , 17, 1900229	3.4	8
80	Effect of extractives in plasma modification of wood surfaces. <i>Surface Innovations</i> , <b>2015</b> , 3, 196-205	1.9	8
79	Experimental and modelling study of organization phenomena in dielectric barrier discharges with structurally inhomogeneous wood substrates. <i>Plasma Sources Science and Technology</i> , <b>2014</b> , 23, 054006	3.5	8
78	Improvement of the emission properties from InGaN/GaN dot-in-a-wire nanostructures after treatment in the flowing afterglow of a microwave N <sub>2</sub> plasma. <i>Nanotechnology</i> , <b>2014</b> , 25, 435606	3.4	8
77	Nonlocal effect of plasma resonances on the electron energy-distribution function in microwave plasma columns. <i>Physical Review E</i> , <b>2012</b> , 86, 015402	2.4	8
76	Simulation of redeposition during platinum etching in argon plasmas. <i>Journal of Applied Physics</i> , <b>2010</b> , 107, 063306	2.5	8
75	Influence of the film properties on the plasma etching dynamics of rf-sputtered indium zinc oxide layers. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2007</b> , 25, 659-665	2.9	8
74	W2B and CrB2 diffusion barriers for Ni/Au contacts to p-GaN. <i>Applied Physics Letters</i> , <b>2007</b> , 91, 042105	3.4	8
73	Influence of the microstructure on the optical characteristics of SrTiO <sub>3</sub> thin films. <i>Journal of Materials Research</i> , <b>2005</b> , 20, 68-74	2.5	8
72	Treatment of graphene films in the early and late afterglows of N <sub>2</sub> plasmas: comparison of the defect generation and N-incorporation dynamics. <i>Plasma Sources Science and Technology</i> , <b>2018</b> , 27, 124004	3.5	8
71	Enhancing the water repellency of wood surfaces by atmospheric pressure cold plasma deposition of fluorocarbon film. <i>RSC Advances</i> , <b>2017</b> , 7, 29159-29169	3.7	7
70	Toward More Sustainable Rechargeable Aqueous Batteries Using Plasma-Treated Cellulose-Based Li-Ion Electrodes. <i>ACS Sustainable Chemistry and Engineering</i> , <b>2020</b> , 8, 4728-4733	8.3	7
69	Aging and Stability of GaN High Electron Mobility Transistors and Light-Emitting Diodes With TiB <sub>2</sub> - and Ir-Based Contacts. <i>IEEE Transactions on Device and Materials Reliability</i> , <b>2008</b> , 8, 272-276	1.6	7
68	Annealing and Measurement Temperature Dependence of W2B- and W2B5-Based Rectifying Contacts to p-GaN. <i>Journal of Electronic Materials</i> , <b>2007</b> , 36, 384-390	1.9	7
67	Increased Schottky barrier heights for Au on n- and p-type GaN using cryogenic metal deposition. <i>Applied Physics Letters</i> , <b>2006</b> , 89, 122106	3.4	7
66	Thermal stability of Ohmic contacts to InN. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 162107	3.4	7

65	Multi-scale investigation in the frequency domain of Ar/HMDSO dusty plasma with pulsed injection of HMDSO. <i>Plasma Sources Science and Technology</i> , <b>2019</b> , 28,	3.5	6
64	Probing plasma-treated graphene using hyperspectral Raman. <i>Review of Scientific Instruments</i> , <b>2020</b> , 91, 063903	1.7	6
63	Unveiling the origin of the anti-fogging performance of plasma-coated glass: Role of the structure and the chemistry of siloxane precursors. <i>Progress in Organic Coatings</i> , <b>2020</b> , 141, 105401	4.8	6
62	Emission spectra from direct current and microwave powered Hg lamps at very high pressure. <i>Journal Physics D: Applied Physics</i> , <b>2013</b> , 46, 455201	3	6
61	Comparison of plasma chemistries for the dry etching of bulk single-crystal zinc-oxide and rf-sputtered indium-zinc-oxide films. <i>Applied Surface Science</i> , <b>2007</b> , 253, 9228-9233	6.7	6
60	Ir-based diffusion barriers for Ohmic contacts to p-GaN. <i>Applied Surface Science</i> , <b>2008</b> , 254, 4134-4138	6.7	6
59	Influence of the positive ion composition on the ion-assisted chemical etch yield of SrTiO <sub>3</sub> films in Ar/F <sub>6</sub> plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2007</b> , 25, 425-431	3.9	6
58	Ion mass dependence of the etch yield of SrTiO <sub>3</sub> films in reactive plasmas. <i>Applied Physics Letters</i> , <b>2005</b> , 87, 131503	3.4	6
57	Experiments and kinetic modeling of the ion energy distribution function at the substrate surface during magnetron sputtering of silver targets in radio frequency argon plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2019</b> , 37, 021301	2.9	5
56	Selective nitrogen doping of graphene due to preferential healing of plasma-generated defects near grain boundaries. <i>Npj 2D Materials and Applications</i> , <b>2020</b> , 4,	8.8	5
55	Highly porous micro-roughened structures developed on aluminum surface using the jet of rotating arc discharges at atmospheric pressure. <i>Journal of Applied Physics</i> , <b>2018</b> , 123, 073302	2.5	5
54	Microstructural and optical properties tuning of BiFeO <sub>3</sub> thin films elaborated by magnetron sputtering. <i>Journal of Materials Science: Materials in Electronics</i> , <b>2015</b> , 26, 3316-3323	2.1	5
53	Evidence of local power deposition and electron heating by a standing electromagnetic wave in electron-cyclotron-resonance plasma. <i>Physical Review E</i> , <b>2014</b> , 90, 033106	2.4	5
52	Measurements of sputtered neutrals and ions and investigation of their roles on the plasma properties during rf magnetron sputtering of Zn and ZnO targets. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2013</b> , 31, 061306	2.9	5
51	Characterization of a low-pressure chlorine plasma column sustained by propagating surface waves using phase-sensitive microwave interferometry and trace-rare-gas optical emission spectroscopy. <i>Journal of Applied Physics</i> , <b>2011</b> , 109, 113304	2.5	5
50	Recent progress on organosilicon coatings deposited on bleached unrefined Kraft paper by non-thermal plasma process at atmospheric pressure. <i>Progress in Organic Coatings</i> , <b>2020</b> , 147, 105865	4.8	5
49	Analysis of transport phenomena during plasma deposition of hydrophobic coatings on porous cellulosic substrates in plane-to-plane dielectric barrier discharges at atmospheric pressure. <i>Plasma Processes and Polymers</i> , <b>2020</b> , 17, 2000091	3.4	5
48	Organization of Dielectric Barrier Discharges in the Presence of Structurally Inhomogeneous Wood Substrates. <i>IEEE Transactions on Plasma Science</i> , <b>2014</b> , 42, 2366-2367	1.3	4

47	Ir-Based Schottky and Ohmic Contacts on n-GaN. <i>Journal of the Electrochemical Society</i> , <b>2007</b> , 154, H584	3.9	4
46	TiO <sub>2</sub> /SiO <sub>2</sub> nanocomposite thin films deposited by direct liquid injection of colloidal solution in an O <sub>2</sub> /HMDSO low-pressure plasma. <i>Journal Physics D: Applied Physics</i> , <b>2021</b> , 54, 085206	3	4
45	Beyond microelectronics with 1,3,5,7-tetramethylcyclotetrasiloxane: A promising molecule for anti-fogging coatings. <i>Materials Chemistry and Physics</i> , <b>2020</b> , 242, 122508	4.4	4
44	Spatially-Resolved Spectroscopic Diagnostics of a Miniature RF Atmospheric Pressure Plasma Jet in Argon Open to Ambient Air. <i>Plasma</i> , <b>2020</b> , 3, 38-53	1.7	4
43	Influence of a square pulse voltage on argon-ethyl lactate discharges and their plasma-deposited coatings using time-resolved spectroscopy and surface characterization. <i>Physics of Plasmas</i> , <b>2018</b> , 25, 103504	2.1	4
42	Emission and absorption diagnostics of a diffuse dielectric barrier discharge with multiple current peaks in helium at atmospheric pressure. <i>Plasma Sources Science and Technology</i> , <b>2019</b> , 28, 085011	3.5	3
41	Determination of the number density of excited and ground Zn atoms during rf magnetron sputtering of ZnO target. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2015</b> , 33, 041302	2.9	3
40	Atmospheric pressure Townsend discharges as a promising tool for the one-step deposition of antifogging coatings from N <sub>2</sub> O/TMCTS mixtures. <i>Plasma Processes and Polymers</i> , <b>2020</b> , 17, 1900186	3.4	3
39	Analysis of the high-energy electron population in surface-wave plasma columns in presence of collisionless resonant absorption. <i>Plasma Sources Science and Technology</i> , <b>2018</b> , 27, 095011	3.5	3
38	Time-resolved analysis of the precursor fragmentation kinetics in an hybrid PVD/PECVD dusty plasma with pulsed injection of HMDSO. <i>Plasma Processes and Polymers</i> , <b>2019</b> , 16, 1900044	3.4	3
37	Nanoparticle synthesis by high-density plasma sustained in liquid organosilicon precursors. <i>Journal of Applied Physics</i> , <b>2017</b> , 122, 243301	2.5	3
36	Correlation between surface chemistry and ion energy dependence of the etch yield in multicomponent oxides etching. <i>Journal of Applied Physics</i> , <b>2009</b> , 106, 063302	2.5	3
35	Effect of Cryogenic Temperature Deposition of Various Metal Contacts on Bulk Single-Crystal n-Type ZnO. <i>Journal of Electronic Materials</i> , <b>2007</b> , 36, 488-493	1.9	3
34	Propagation of surface waves in two-plasma systems bounded by a metallic enclosure. <i>Journal of Plasma Physics</i> , <b>2001</b> , 66, 349-362	2.7	3
33	Multi-pass deposition of organosilicon-based superhydrophobic coatings in atmospheric pressure plasma jets. <i>Thin Solid Films</i> , <b>2020</b> , 714, 138369	2.2	3
32	In situ investigation of magnetron sputtering plasma used for the deposition of multiferroic BiFeO <sub>3</sub> thin films. <i>Journal of Materials Science: Materials in Electronics</i> , <b>2017</b> , 28, 15749-15753	2.1	2
31	Time and space-resolved experimental investigation of the electron energy distribution function of a helium capacitive discharge at atmospheric pressure. <i>Journal Physics D: Applied Physics</i> , <b>2019</b> , 52, 245202	2.2	2
30	Spatially Modulated Emission of ECR Plasmas in Helium. <i>IEEE Transactions on Plasma Science</i> , <b>2014</b> , 42, 2762-2763	1.3	2

29	Ir/Au Ohmic Contacts on Bulk, Single-Crystal n-Type ZnO. <i>Journal of the Electrochemical Society</i> , <b>2007</b> , 154, H161	3.9	2
28	Nitride-based Ohmic and Schottky Contacts to GaN. <i>ECS Transactions</i> , <b>2007</b> , 6, 191-199	1	2
27	Comment on Plasma etching of high dielectric constant materials on silicon in halogen plasma chemistries by L. Sha and J. P. Chang [J. Vac. Sci. Technol. A 22, 88 (2004)]. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2005</b> , 23, 720-721	2.9	2
26	Time-resolved imaging of pulsed positive nanosecond discharge on water surface: plasma dots guided by water surface. <i>Plasma Sources Science and Technology</i> , <b>2020</b> , 29, 115017	3.5	2
25	Modification of the optical properties and nano-crystallinity of anatase TiO <sub>2</sub> nanoparticles thin film using low pressure O <sub>2</sub> plasma treatment. <i>Thin Solid Films</i> , <b>2020</b> , 709, 138212	2.2	2
24	Modification of microfibrillated cellulosic foams in a dielectric barrier discharge at atmospheric pressure. <i>Plasma Processes and Polymers</i> , <b>2021</b> , 18, 2000158	3.4	2
23	Response surface methodology as a predictive tool for the fabrication of coatings with optimal anti-fogging performance. <i>Thin Solid Films</i> , <b>2021</b> , 718, 138482	2.2	2
22	On the rotational-translational equilibrium in non-thermal argon plasmas at atmospheric pressure. <i>Plasma Sources Science and Technology</i> , <b>2021</b> , 30, 035020	3.5	2
21	Interaction of N and O atoms with hardwood and softwood surfaces in the flowing afterglow of N <sub>2</sub> -O <sub>2</sub> microwave plasmas. <i>Plasma Processes and Polymers</i> , <b>2018</b> , 15, e1800035	3.4	1
20	Spatially resolved electron density and electron energy distribution function in Ar magnetron plasmas used for sputter-deposition of ZnO-based thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2015</b> , 33, 061310	2.9	1
19	Improved Long-Term Thermal Stability At 350°C Of TiB <sub>2</sub> -Based Ohmic Contacts On AlGaN/GaN High Electron Mobility Transistors. <i>Journal of Electronic Materials</i> , <b>2007</b> , 36, 379-383	1.9	1
18	Thermal Stability of Nitride-Based Diffusion Barriers for Ohmic Contacts to n-GaN. <i>Journal of Electronic Materials</i> , <b>2007</b> , 36, 1662-1668	1.9	1
17	Deep etch-induced damage during ion-assisted chemical etching of sputtered indium-zinc-oxide films in Ar/CH <sub>4</sub> /H <sub>2</sub> plasmas. <i>Thin Solid Films</i> , <b>2008</b> , 516, 2869-2873	2.2	1
16	Reduction of Dry Etch Damage to GaAs Using Pulse-Time Modulated Plasmas. <i>Electrochemical and Solid-State Letters</i> , <b>2007</b> , 10, H139		1
15	Growth and patterning of strontium-titanate-oxide thin films for optical devices applications. <i>Materials Research Society Symposia Proceedings</i> , <b>2004</b> , 817, 141		1
14	Ultra-high-resolution optical absorption spectroscopy of DC plasmas at low pressure using a supercontinuum laser combined with a laser line tunable filter and a HyperFine spectrometer. <i>Journal Physics D: Applied Physics</i> , <b>2021</b> , 54, 085204	3	1
13	Plasma-graphene interactions: combined effects of positive ions, vacuum-ultraviolet photons, and metastable species. <i>Journal Physics D: Applied Physics</i> , <b>2021</b> , 54, 295202	3	1
12	Deposition of TiO <sub>2</sub> -SiO <sub>2</sub> nanocomposite coatings using atmospheric-pressure plasmas <b>2016</b> ,		1

11	Incorporation-limiting mechanisms during nitrogenation of monolayer graphene films in nitrogen flowing afterglows. <i>Nanoscale</i> , <b>2021</b> , 13, 2891-2901	7.7	1
10	Probing suprathermal electrons by trace rare gases optical emission spectroscopy in low pressure dipolar microwave plasmas excited at the electron cyclotron resonance. <i>Physics of Plasmas</i> , <b>2018</b> , 25, 093511	2.1	1
9	Refined analysis of current-voltage characteristics in Townsend dielectric barrier discharges in nitrogen at atmospheric pressure. <i>Journal Physics D: Applied Physics</i> , <b>2021</b> , 54, 095204	3	0
8	Spatio-temporal dynamics of a nanosecond pulsed microwave plasma ignited by time reversal. <i>Plasma Sources Science and Technology</i> , <b>2020</b> , 29, 125017	3.5	0
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